Supporting Information

A dual-functional additive improves the performance of molecular bulk heterojunction photovoltaic cells

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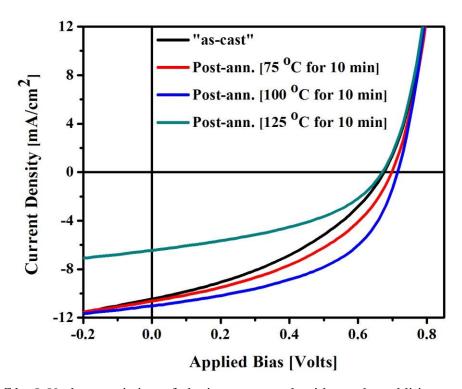


Figure S1. *J*–*V* characteristics of devices prepared without the additive and subjected to different post-annealing temperatures.

Table S1. Photovoltaic characteristics of devices prepared without the additive and subjected to different post-annealing temperatures.

Annealing Temp. [°C]	$J_{ m sc}$ [mA/cm ²]	$V_{ m oc} \ [{ m V}]$	FF [%]	PCE [%]
"as-cast"	10.46	0.68	38.66	2.75
75°C	10.60	0.70	42.45	3.15
100 °C	10.20	0.71	48.33	3.50
125°C	6.45	0.67	43.04	1.86

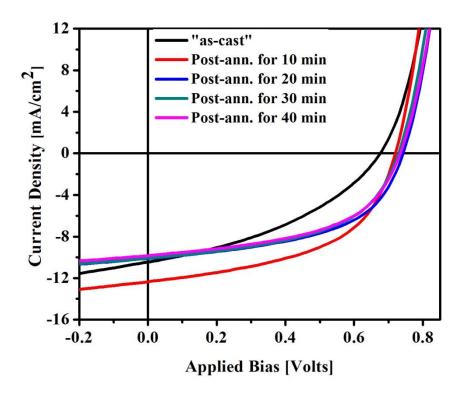


Figure S2. *J–V* characteristics of devices prepared with 0.1% of the additive CP3MS and post-annealing at 100 °C for different lengths of time.

Table S2. Photovoltaic characteristics of devices incorporating 0.1% of the additive that had been subjected to post-annealing at 100 °C for different lengths of time.

Annealing Time [min]	$J_{\rm sc}$ [mA/cm ²]	$V_{ m oc}$ [V]	FF [%]	PCE [%]
"as-cast"	10.46	0.68	38.66	2.75
10	12.36	0.72	51.14	4.55
20	10.13	0.74	52.43	3.93
30	10.09	0.73	51.45	3.79
40	9.85	0.73	51.87	3.73

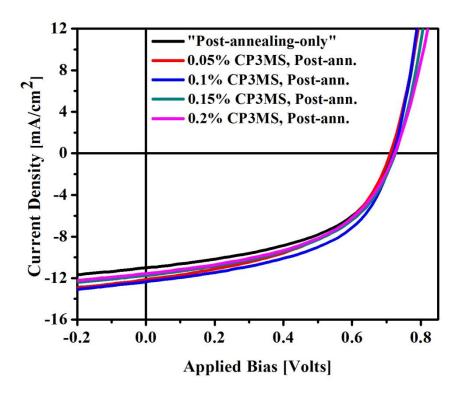


Figure S3. *J–V* characteristics of devices prepared with different CP3MS concentrations and post-annealing at 100 °C for 10 min.

Al-cathode smoothly removed





Active layer attached with Al-cathode after peel-off

Post-annealed device

Device without Post annealing

Figure S4. Digital camera images showing the effect of post-annealing treatment on the interface between the active layer and the metal cathode.

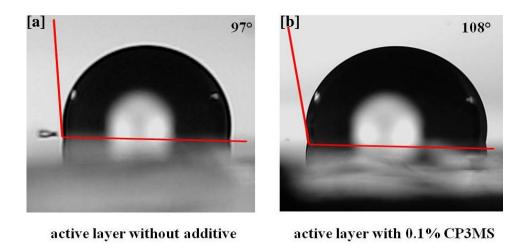


Figure S5. Images of contact angles of active layers without additive (a) and with 0.1% CP3MS additive (b)

Scheme S1. Chemical structure of benzodithiophene (BDT)-based molecule (TBDTCNR)

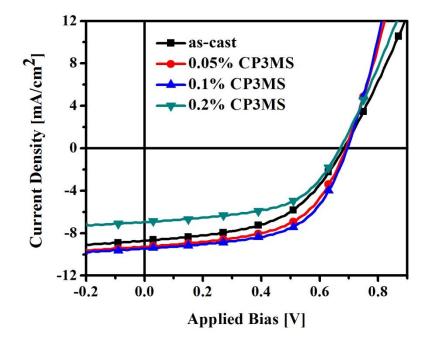


Figure S6: *J–V* characteristics of devices prepared with different CP3MS concentrations for benzodithiophene (BDT)-based molecule (TBDTCNR)

Table S3. Photovoltaic characteristics of devices prepared with different CP3MS concentrations for benzodithiophene (BDT)-based molecule (TBDTCNR).

Additive Conc. [%]	$J_{ m sc}$ [mA/cm ²]	<i>V</i> _{oc} [V]	FF [%]	PCE [%]
"as-cast"	8.70	0.68	51.56	3.05
0.05% CP3MS	9.26	0.69	55.25	3.53
0.10% CP3MS	9.46	0.70	57.38	3.80
0.20% CP3MS	6.92	0.67	55.22	2.56